

REMARKS

Applicant requests favorable reconsideration and allowance of the subject application in view of the preceding amendments and the following remarks.

Claims 37-41 and 46-51 are presented for consideration. Claims 37, 40, 46 and 51 are independent. Claims 42-45 have been canceled without prejudice or disclaimer. Claims 37, 40 and 41 have been amended to clarify features of the present invention, while claims 46-51 have been added to recite additional features of the subject invention. Support for these changes and claims can be found in the original application, as filed. Therefore, no new matter has been added.

Applicant requests favorable reconsideration and withdrawal of the objection and rejections set forth in the above-noted Office Action.

Claim 40 was objected to as being in improper dependent form. To expedite prosecution, claim 40 has been amended to substantively incorporate the subject matter of independent claim 37, from which it previously depended. Applicant submits that these changes overcome this objection. Such favorable indication is requested.

Turning now to the art rejections, claims 37-40 and 42-45 were rejected under 35 U.S.C. § 102(e) as being anticipated by U.S. Patent No. 6,462,807 to Nishi. Claim 41 was rejected under 35 U.S.C. § 103(a) as being unpatentable over the Nishi patent. Applicant submits that the cited art does not teach many features of the present invention, as previously recited in these claims. Therefore, these rejections are respectfully traversed. Nevertheless, Applicant submits that independent claims 37, 40, 46 and 51, for example, as presented, amplify the distinctions between the present invention and the cited art.

In one aspect of the present invention, independent claim 37 recites an exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, while the substrate and the reticle are scanned. The apparatus includes a reticle stage configured to hold the reticle and to move, a substrate stage configured to hold the substrate and to move, an interface configured to input information of a condition of the exposure, and a controller configured to select, as an exposure method to be performed, an exposure method in which the exposure is performed while the reticle stage and the substrate stage are accelerated, based on the input information.

In another aspect of the present invention, independent claim 40 recites a method of manufacturing a device. The method includes steps of performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus, developing the exposed substrate, and processing the developed substrate to manufacture the device. The exposure apparatus performs the exposure while each of the substrate and the reticle is scanned in accordance with a target speed. The apparatus includes (i) a reticle stage configured to hold the reticle and to move, (ii) a substrate stage configured to hold the substrate and to move, (iii) an interface configured to input information of a condition of the exposure, and (iv) a controller configured to select, as an exposure method to be performed, an exposure method in which the exposure is performed while the reticle stage and the substrate stage are accelerated, based on the input information.

In a further aspect of the present invention, independent claim 46 recites an exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, while the substrate and the reticle are scanned. The apparatus includes a reticle stage configured to hold the reticle and to move, a substrate stage configured to hold the substrate and to move, an interface configured to input information of a condition of the exposure, and a controller

configured to select, as an exposure method to be performed, an exposure method in which the exposure is performed while the reticle stage and the substrate stage are decelerated, based on the input information.

In still another aspect of the present invention, independent claim 51 recites a method of manufacturing a device. The method includes steps of performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus, developing the exposed substrate, and processing the developed substrate to manufacture the device. The exposure apparatus performs the exposure while each of the substrate and the reticle is scanned in accordance with a target speed. The apparatus includes (i) a reticle stage configured to hold the reticle and to move, (ii) a substrate stage configured to hold the substrate and to move, (iii) an interface configured to input information of a condition of the exposure, and (iv) a controller configured to select, as an exposure method to be performed, an exposure method in which the exposure is performed while the reticle stage and the substrate stage are decelerated, based on the input information.

Applicant submits that the cited art does not teach or suggest such features of the present invention as recited in the independent claims.

The Nishi patent relates to an exposure apparatus that is capable of selectively switching among a plurality of exposure modes. In this apparatus, an exposure time to be required for one substrate based on a layout of shot regions and a quantity of exposure to be required for executing exposure are calculated. The exposure apparatus in the Nishi patent then selects an exposure mode with an entirely shorter exposure time.

Applicant submits, however, that the Nishi patent does not teach or suggest salient features of Applicant's present invention, as recited in the independent claims. Namely, that patent does not teach or suggest anything regarding selecting, as an exposure method to be

performed, an exposure method in which the exposure is performed while a reticle stage and a substrate stage are accelerated, based on input information, in the manner of the present invention recited in independent claims 37 and 40. Likewise, that patent, does not teach or suggest anything regarding selecting, as an exposure method to be performed, an exposure method in which the exposure is performed while a reticle stage and a substrate stage are decelerated, based on input information, in the manner of the present invention recited in independent claims 46 and 51. Accordingly, the Nishi patent does not teach or suggest many features of the present invention, as recited in the independent claims.

For the reasons noted above, Applicant submits that the present invention, as recited in independent claims 37, 40, 46 and 51, is patentably defined over the cited art.

Dependent claims 38, 39, 41 and 47-50 also should be deemed allowable, in their own right, for defining other patentable features of the present invention in addition to those recited in their respective independent claims. Individual consideration of these dependent claims is requested.

Applicant submits that the instant application is in condition for allowance. Applicant, therefore, requests favorable reconsideration, withdrawal of the objection and rejections set forth in the above-noted Office Action and an early Notice of Allowance.

Applicant's undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should be directed to our address listed below.

Respectfully submitted,



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